

ABSTRACT

A substrate cleaning roll capable of cleaning the outermost edge of a substrate, and a substrate cleaning apparatus that uses the substrate cleaning roll are to be provided. A substrate cleaning apparatus (10) includes: spindles (11) that hold a substrate (S); a lower substrate cleaning roll (13) that has a cylindrical shape and scrubs a surface of the substrate (S) by rotating about the rotational axis in the longitudinal direction while in contact with the substrate (S) in such a manner that the longitudinal direction becomes parallel to the surface of the substrate (S); a vertical drive mechanism that pushes the lower substrate cleaning roll (13) against the lower surface of the substrate (S) so that the longitudinal direction becomes parallel to the surface of the substrate (S); and a rotative drive mechanism that rotates the lower substrate cleaning roll (13) about the rotational axis, the lower substrate cleaning roll (13) being pushed against the lower surface of the substrate (S) by the vertical drive mechanism. The lower substrate cleaning roll (13) has edge nodules (135) at least at one end thereof in the longitudinal direction. Each edge nodule 135 has a sloping surface (1351) to be in contact with the side portion (R) as the outermost edge of a bevel portion (B) at the rim of the substrate (S) when the lower substrate cleaning roll (13) comes into contact with the substrate (S).